Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	1	(pretreat$5 and polysilicon and titanium and nitrogen and (vapor adj deposition precursor)).clm.	US-PGPUB; USPAT; USOCR	OR	ON	2005/10/24 11:52
L6	2	(treat$5 and chamber and polysilicon and titanium and nitrogen and (vapor adj deposition precursor)).clm.	US-PGPUB; USPAT; USOCR	OR	ON	2005/10/24 11:53